

ABSTRACT

The present invention provides a method of manufacturing a PDP that prevents a defect from occurring in a structure of the PDP; and also suppresses retroflexion, exfoliation, and the like, of the structure. In photolithography, exposure is performed twice with a first and a second photomasks, each having a different aperture width, but the same exposure pattern. The amount of exposure is different between first exposure region (A') through the first photomask; and second exposure region (B') through the second photomask.